

AMENDMENT

In response to the Advisory Action of May 12, 2003 please amend the above-identified application as follows:

**In the Claims:**

Please amend claim 1 as follows:

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1. (THRICE AMENDED) A polishing-dressing head for a polishing apparatus comprising:

a plurality of substrate head assemblies each having a lower nesting surface opposed to an upper surface of a polishing pad, said lower nesting surface releasably holds a substrate to be polished, said substrate head assemblies, each rotating along a central axis thereof and polishing the substrates on an outer radial portion of said rotating polishing pad;

annular dressing rings for dressing said polishing pad, said dressing rings are positioned coaxially encircling each nested substrate, said annular dressing rings are (removably attached) to said lower surface of said substrate head assemblies.

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